

Notice of References Cited	Application/Control No. 10/785,505	Applicant(s)/Patent Under Reexamination BANERJEE ET AL.	
	Examiner Belur V Keshavan	Art Unit 2825	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,366,917	11-1994	Watanabe et al.	438/398
	B	US-5,372,962	12-1994	Hirota et al.	438/398
	C	US-5,385,863	01-1995	Tatsumi et al.	438/398
	D	US-5,405,801	04-1995	Han et al.	438/386
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	M. Ino et al., Rugged surface polycrystalline silicon film deposition and its application in a stacked dynamic random access memory capacitor electrode, 14 J. Vac Sci. Technol. B 14(2), Mar/Apr 1996, pp 751-756.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.